

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/1591243/publications.pdf Version: 2024-02-01



\\/FLLL

#	Article	IF	CITATIONS
1	Controllable resistive switching of STO:Ag/SiO2-based memristor synapse for neuromorphic computing. Journal of Materials Science and Technology, 2022, 97, 254-263.	10.7	41
2	Mimicking Neuroplasticity via Ion Migration in van der Waals Layered Copper Indium Thiophosphate. Advanced Materials, 2022, 34, e2104676.	21.0	46
3	A Modified SiO ₂ -Based Memristor with Reliable Switching and Multifunctional Synaptic Behaviors. Journal of Physical Chemistry Letters, 2022, 13, 884-893.	4.6	14
4	Artificial synapse arrays based on SiOx/TiOx memristive crossbar with high uniformity for neuromorphic computing. Applied Physics Letters, 2022, 120, .	3.3	7
5	Nanostructured Materials and Architectures for Advanced Optoelectronic Synaptic Devices. Advanced Functional Materials, 2022, 32, .	14.9	45
6	Multifunctional Analog Resistance Switching of Si ₃ N ₄ -Based Memristors through Migration of Ag ⁺ lons and Formation of Si-Dangling Bonds. Journal of Physical Chemistry Letters, 2022, 13, 5101-5108.	4.6	6
7	Photoelectronic synaptic performance of SiOy/a-Si1-xRux bilayer based memristors. , 2021, , .		1
8	Optically stimulated synaptic devices based on silicon-tin alloyed thin film. , 2021, , .		0
9	Colorâ€Recognizing Siâ€Based Photonic Synapse for Artificial Visual System. Advanced Intelligent Systems, 2020, 2, 2000107.	6.1	21
10	Coexistence of Digital and Analog Resistive Switching Behaviours in Ag/CuAlO2/TiO2/p++-Si Memristor. Journal of Physics: Conference Series, 2020, 1637, 012053.	0.4	3
11	Analog Switching and Artificial Synaptic Behavior of Ag/SiOx:Ag/TiOx/p++-Si Memristor Device. Nanoscale Research Letters, 2020, 15, 30.	5.7	65
12	Bi-Polar Synaptic Behavior of Pt/SiO _x :Ag/TiO _x /p ⁺⁺ - Si Memristor. Materials Science Forum, 2020, 984, 104-109.	0.3	0
13	Synaptic learning and memory functions in SiO ₂ :Ag/TiO ₂ based memristor devices. Journal Physics D: Applied Physics, 2020, 53, 175102.	2.8	16
14	Memristive Behaviour of Ag-doped-HfO ₂ Thin Films Prepared by Magnetron Sputtering. Journal of Physics: Conference Series, 2020, 1637, 012024.	0.4	0
15	Structural Variation and Its Influence on the 1/ <i>f</i> Noise of a-Si _{1â~'<i>x</i>} Ru _{<i>x</i>} Thin Films Embedded with Nanocrystals. Chinese Physics Letters, 2019, 36, 028101.	3.3	0
16	Inhomogeneous crystallization of <scp>aâ€Si</scp> thin films irradiated by femtosecond laser. Journal of Raman Spectroscopy, 2019, 50, 793-801.	2.5	7
17	A novel design of a-Si based memristor with optical readout functionality utilizing silicon prism. , 2019, , .		0
18	An Artificial Bio-Synapse Based on Ag/a-Si:Ag/a-Si/X Memristors With Different Bottom Electrode X. IOP Conference Series: Materials Science and Engineering, 2018, 452, 042160.	0.6	0

Wei Li

#	Article	IF	CITATIONS
19	Enhanced near-infrared absorber: two-step fabricated structured black silicon and its device application. Nanoscale Research Letters, 2018, 13, 316.	5.7	9
20	Low-Dimensional Materials and State-of-the-Art Architectures for Infrared Photodetection. Sensors, 2018, 18, 4163.	3.8	19
21	Broadband optoelectronic synaptic devices based on silicon nanocrystals for neuromorphic computing. Nano Energy, 2018, 52, 422-430.	16.0	150
22	Structural and optoelectronic properties of a-Si:H: A new analysis based on spectroscopic ellipsometry. Vacuum, 2017, 146, 409-421.	3.5	1
23	Comparison of different etching methods on the morphology and semiconductor characters of black silicon. IOP Conference Series: Materials Science and Engineering, 2017, 250, 012015.	0.6	3
24	Structural and Optoelectronic Properties of a-SiOx: Ag Films Used for Ag/SiOx/p-Si Memristor. IOP Conference Series: Materials Science and Engineering, 2017, 250, 012027.	0.6	0
25	The Enhanced Light Absorptance and Device Application of Nanostructured Black Silicon Fabricated by Metal-assisted Chemical Etching. Nanoscale Research Letters, 2016, 11, 322.	5.7	27
26	The realization of optical switching generated from the combination of Ag/a-Si/p-Si memristor and silicon waveguide. Proceedings of SPIE, 2016, , .	0.8	0
27	The relation of structure and dispersion to amorphous silicon silver thin films. Materials Letters, 2016, 185, 5-8.	2.6	7
28	Improvement of metal-semiconductor contact on silicon microstructured surface by electroless nickel technique. Proceedings of SPIE, 2016, , .	0.8	0
29	Band engineering of amorphous silicon ruthenium thin film and its near-infrared absorption enhancement combined with nano-holes pattern on back surface of silicon substrate. Applied Surface Science, 2016, 384, 487-491.	6.1	4
30	Raman analysis of amorphous silicon ruthenium thin films embedded with nanocrystals. Journal of Raman Spectroscopy, 2015, 46, 619-623.	2.5	11
31	Polarization-sensitive broadband photodetector using a black phosphorus vertical p–n junction. Nature Nanotechnology, 2015, 10, 707-713.	31.5	1,007
32	Performance enhancement of amorphous indium-zinc-oxide thin film transistors by microwave annealing. Applied Surface Science, 2015, 357, 1915-1919.	6.1	10
33	Structural variation and electrical properties of amorphous silicon ruthenium thin films embedded with nanocrystals. Materials Letters, 2015, 143, 80-83.	2.6	6
34	Enhancement of c-Si surface passivation quality by increasing in situ H2 flow rate. Materials Letters, 2015, 161, 175-177.	2.6	10
35	Contact resistance improvement using interfacial silver nanoparticles in amorphous indium-zinc-oxide thin film transistors. Applied Physics Letters, 2014, 105, .	3.3	12
36	Metamaterial Perfect Absorber Based Hot Electron Photodetection. Nano Letters, 2014, 14, 3510-3514.	9.1	591

Wei Li

#	Article	IF	CITATIONS
37	Black silicon with self-cleaning surface prepared by wetting processes. Nanoscale Research Letters, 2013, 8, 351.	5.7	33
38	Investigation of nanocrystallization of a-Si1â^'xGex:H thin films diluted with argon in the PECVD system. Journal of Non-Crystalline Solids, 2013, 365, 37-41.	3.1	9
39	Dispersion model for optical constants of a-Si:H. Physica B: Condensed Matter, 2013, 431, 120-126.	2.7	7
40	Structural evolution and electronic properties of phosphorus-doped hydrogenated amorphous silicon thin films deposited by PECVD. Science China Technological Sciences, 2013, 56, 103-108.	4.0	4
41	Microwave irradiation induced structural evolution of a-Si:H thin film before crystallization. Materials Letters, 2013, 100, 156-158.	2.6	4
42	Boron-doped nanocrystalline silicon germanium thin films for uncooled infrared bolometer applications. Infrared Physics and Technology, 2013, 58, 32-35.	2.9	12
43	Effect of gas temperature on the structural and optoelectronic properties of a-Si:H thin films deposited by PECVD. Surface and Coatings Technology, 2013, 214, 131-137.	4.8	8
44	New paramagnetic centre and high conductivity in a-Si1â^'xRux : H thin films. Journal Physics D: Applied Physics, 2013, 46, 475107.	2.8	3
45	New Paramagnetic Center and High Conductivity in a-Si1-xRux:H Thin Films. Materials Research Society Symposia Proceedings, 2013, 1617, 57-62.	0.1	0
46	Structure and electronic states in a-Si:H thin films. Journal of Materials Science, 2012, 47, 5121-5127.	3.7	4
47	Hydrogen bonding in hydrogenated amorphous silicon thin films prepared at different precursor gas temperatures with undiluted silane. Science China Technological Sciences, 2011, 54, 2310-2314.	4.0	3
48	Origins of 1/f noise in nanostructure inclusion polymorphous silicon films. Nanoscale Research Letters, 2011, 6, 281.	5.7	30
49	Raman characterization of the structural evolution in amorphous and partially nanocrystalline hydrogenated silicon thin films prepared by PECVD. Journal of Raman Spectroscopy, 2011, 42, 415-421.	2.5	71
50	Structural evolution and optical characterization in argon diluted Si:H thin films obtained by plasma enhanced chemical vapor deposition. Central South University, 2010, 17, 1163-1171.	0.5	0
51	Raman and ellipsometric characterization of hydrogenated amorphous silicon thin films. Science in China Series D: Earth Sciences, 2009, 52, 339-343.	0.9	4
52	Noise in boron doped amorphous/microcrystallization silicon films. Applied Surface Science, 2008, 254, 3274-3276.	6.1	5
53	Influence of microcrystallization on noise in boronâ€doped silicon film. Physica Status Solidi (A) Applications and Materials Science, 2007, 204, 4292-4297.	1.8	3
54	Effect on Resistive Switching by Inserting TiO _x Thin Layer in SiO _x : Ag-Based Memristor. Materials Science Forum, 0, 984, 97-103.	0.3	2